

[single-layer reflection]
 (Chapter 5.5.4 in *Elements*)

A simple example

A simple example is that of a single layer of nickel metal on a thick substrate of silicon. Figure 5-SLR1 illustrates.

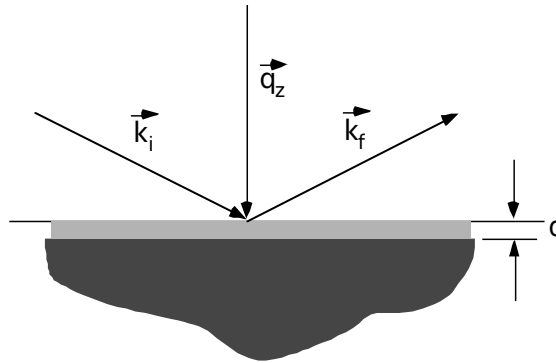


Figure 5-SLR1. Reflection from a single layer on an infinite substrate.

The algorithm sketched previously requires a computer to carry out the matrix multiplications for many-layered systems and in general situations having declared the variables complex. The case of Fig. 5-SLR1 is a tractable example, a single layer on an infinite substrate: nickel on silicon. Table 5-SLR1 summarizes the parameters.

Table 5-SLR1. Parameters of nickel and silicon

Material	Atomic density, ρ , at/cm ³	Coherent scattering length, b , Fm	Coherent scattering length, density, ρb , Å ⁻²	Critical wave number, q_{cr} , Å ⁻¹	Thickness, d , Å
^{nat} Ni	9.143×10^{22}	10.3	9.417×10^{-6}	0.02176	100.
Si	5.00×10^{22}	4.149	2.073×10^{-6}	0.01021	Infinite

For the one-layer case, the matrix product has only a single factor,

$$\mathbf{M}(q) = \begin{pmatrix} \cos x & \frac{1}{\eta} \sin x \\ -\eta \sin x & \cos x \end{pmatrix} = \begin{pmatrix} s & t \\ u & v \end{pmatrix}, \quad (5-SLR1)$$

where

$$x = \eta dq/2 \quad (5-SLR2)$$

for the nickel layer and

$$a' = \frac{\eta_b t + u + i(v - \eta_b s)}{\eta_b t - u + i(v + \eta_b s)} = \frac{\left(\frac{\eta_b - \eta}{\eta}\right) \tan x + i(1 - \eta_b)}{\left(\frac{\eta_b + \eta}{\eta}\right) \tan x + i(1 + \eta_b)}, \quad (5\text{-SLR3})$$

so that when the η 's are real, that is, when $q > \text{Max}[q_{c \text{ layer}}, q_{c \text{ b}}]$,

$$R(q) = |a'|^2 = \frac{\left(\frac{\eta_b - \eta}{\eta}\right)^2 \tan^2 x + (1 - \eta_b)^2}{\left(\frac{\eta_b + \eta}{\eta}\right)^2 \tan^2 x + (1 + \eta_b)^2}. \quad (5\text{-SLR4})$$

If there is no backing, that is, for a free-standing foil, $\eta_b = 1$ and

$$R(q) = \frac{1}{q^4} \frac{(16\pi\rho b)^2 \tan^2(\eta d q / 2)}{(1 + \eta^2)^2 \tan^2(\eta d q / 2) + 4\eta^2}. \quad (5\text{-SLR5})$$

For the substrate alone, $d = 0$ and

$$R(q) = \frac{(1 - \eta_b)^2}{(1 + \eta_b)^2}. \quad (5\text{-SLR6})$$

These expressions are valid for the nickel-only and nickel-on-silicon cases only when $q > q_{c \text{ Ni}} = 0.02176 \text{ \AA}^{-1}$.

When $q_{c \text{ b}} < q < q_{c \text{ Ni}}$, η and therefore x become pure imaginary,

$$\eta \rightarrow i\eta'' = \sqrt{\left|1 - \left(\frac{q_c}{q}\right)^2\right|}, \text{ etc., and } x \rightarrow ix'', \quad (5\text{-SLR7})$$

so that

$$R(q) = \frac{\left(\frac{\eta_b + \eta''}{\eta''}\right)^2 \tanh^2 x'' + (1 - \eta_b)^2}{\left(\frac{\eta_b - \eta''}{\eta''}\right)^2 \tanh^2 x'' + (1 + \eta_b)^2}. \quad (5\text{-SLR8})$$

When $q < q_{c,b}$, η_b also becomes pure imaginary,

$$\eta_b \rightarrow i\eta_b'', \quad (5\text{-SLR9})$$

so that

$$a' = \frac{i \left(\frac{\eta_b''}{\eta''} - i\eta'' \right) \tanh x + i(1 - i\eta_b'')}{i \left(\frac{\eta_b''}{\eta''} + i\eta'' \right) \tanh x + i(1 + i\eta_b'')}, \quad (5\text{-SLR10})$$

in which the numerator and denominator are complex conjugates, therefore

$$R(q) = |a'|^2 = 1. \quad (5\text{-SLR11})$$

We leave the proof of these last results as an exercise for the reader.

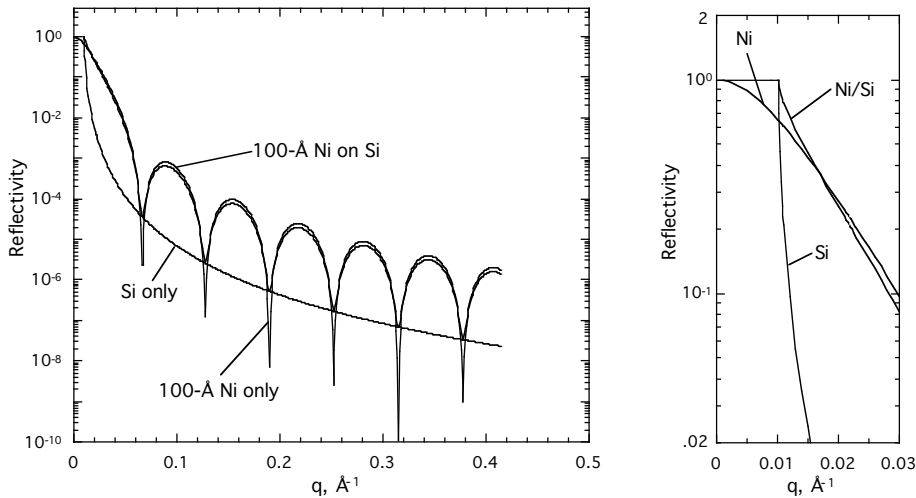


Figure 5-SLR2. The reflectivity of a 100-Å nickel film on an infinitely thick silicon substrate. Smooth curve, substrate only. Upper curve, 100-Å nickel on silicon. Lower curve, 100-Å nickel alone. Right, expanded view of the low- q region.

Figure 5-SLR2 shows the results of calculations using this formulation and the parameters of Table 5-SLR1, showing the reflectivity for the silicon substrate alone, the 100-Å nickel layer

alone, and the nickel layer on the substrate. The reflectivity for the substrate is the lower envelope of the reflectivity of the nickel layer on the substrate.